

Physics of Materials

EPFL

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High Resolution Scanning Electron Microscopy (STEM)

Masters Course PHYS-307

Fall 2024

Why do we use *electrons* as a probe?

High energy = short wavelengths= high spatial resolution

Electromagnetic radiation: $E = hc/\lambda$ so if $\lambda < 5 \text{ nm}$, $E > 1 \text{ keV}$

Electron wavelength according to de Broglie equation: $\lambda = h/p$

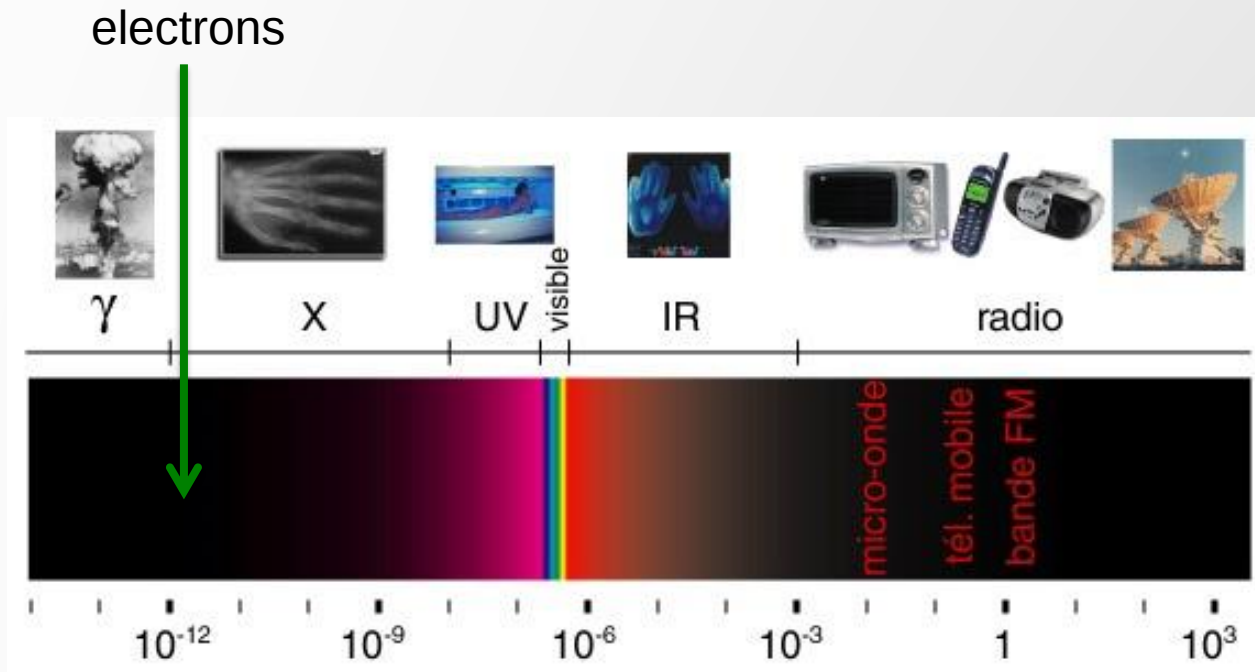
with $p = m_0 v = (2m_0 eV)^{1/2}$

non relativistic (<50keV):

$$\lambda = \frac{h}{(2m_0 eV)^{1/2}}$$

Relativistic correction
(>50keV or >1% speed) :

$$\lambda = \frac{h}{\left[2m_0 eV \left(1 + \frac{eV}{2m_0 c^2} \right) \right]^{1/2}}$$



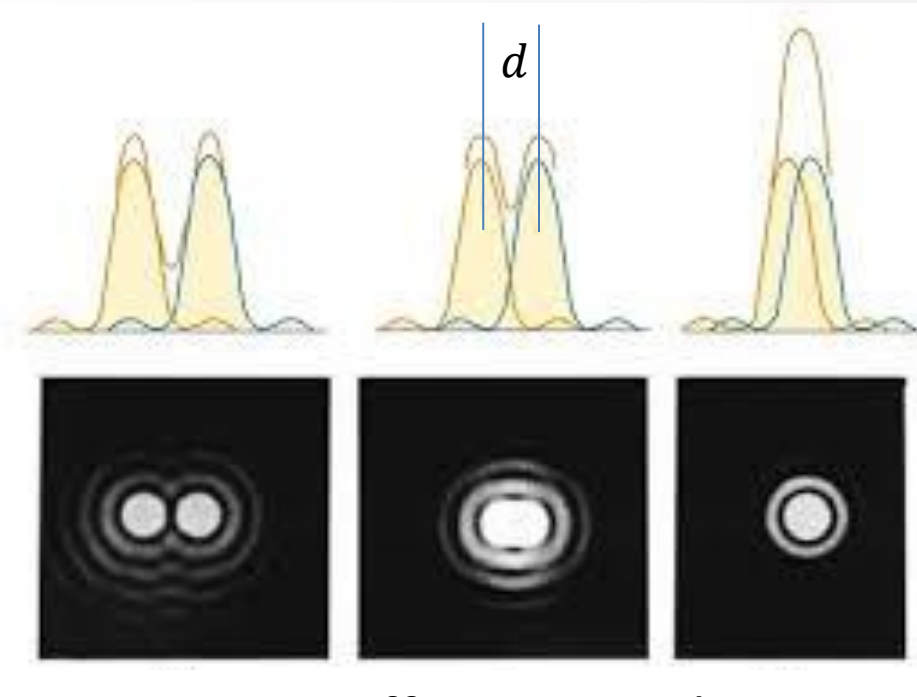
Why do we use *electrons* as probe?

<i>Electron charge (e)</i>	$-1.602 \times 10^{-19} \text{ C}$
<i>1 eV</i>	$1.602 \times 10^{-19} \text{ J}$
<i>Electron rest mass (m_0)</i>	$9.109 \times 10^{-31} \text{ kg}$
<i>Electron rest energy ($m_0 c^2$)</i>	511 keV
<i>Kinetic energy (charge x tension)</i>	$1.602 \times 10^{-19} \text{ Nm (per 1 volt)}$
<i>Plank's constant (h)</i>	$6.626 \times 10^{-34} \text{ N-m-s}$
<i>1 amp</i>	1 C/sec
<i>Light speed in vacuum (c)</i>	$2.998 \times 10^8 \text{ m/sec}$

Accelerating voltage [KV]	Nonrelativistic λ [nm]	Relativistic λ [nm]	Mass [$\times m_0$]	Velocity [$\times 10^8 \text{ m/s}$]
1	0.03879	0.03878	1.002	0.13
10	0.01227	0.01221	1.02	0.42
80	0.00434	0.00418	1.157	1.1
200	0.00274	0.00251	1.391	1.59
300	0.00224	0.00197	1.587	1.82
1000	0.00123	0.00087	2.957	2.44

Why do we use electron as a probe?

Raleigh's Criterion



Airy Diffraction Disks

$$d = 0.61 \frac{\lambda}{n \sin \theta} = 0.61 \frac{\lambda}{\beta}$$

Green light : $\lambda \approx 532$ nm,
 β (objective collection angle) ~ 1 rad

$n = 1.7$ for oil immersion lens

*** $d = 200$ nm

Electrons 200 keV : $\lambda \approx 0.00251$ nm

$n = 1$ for vacuum

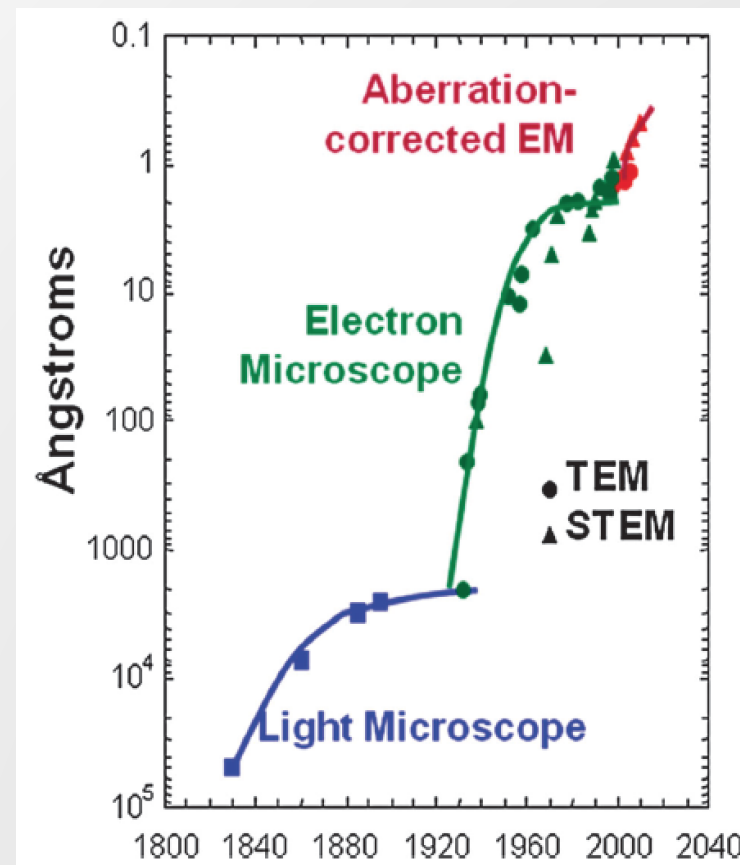
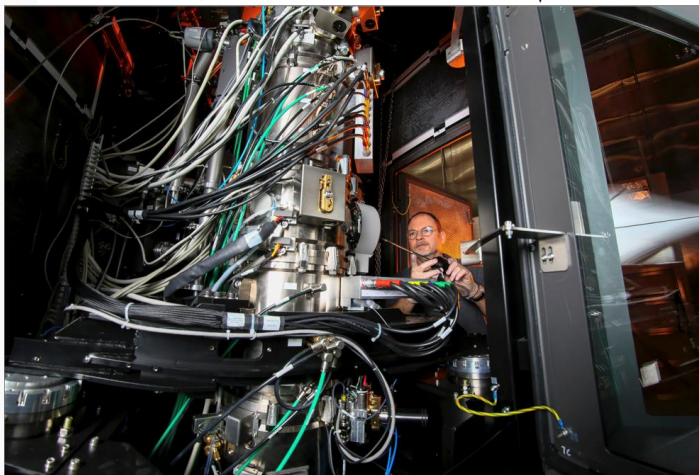
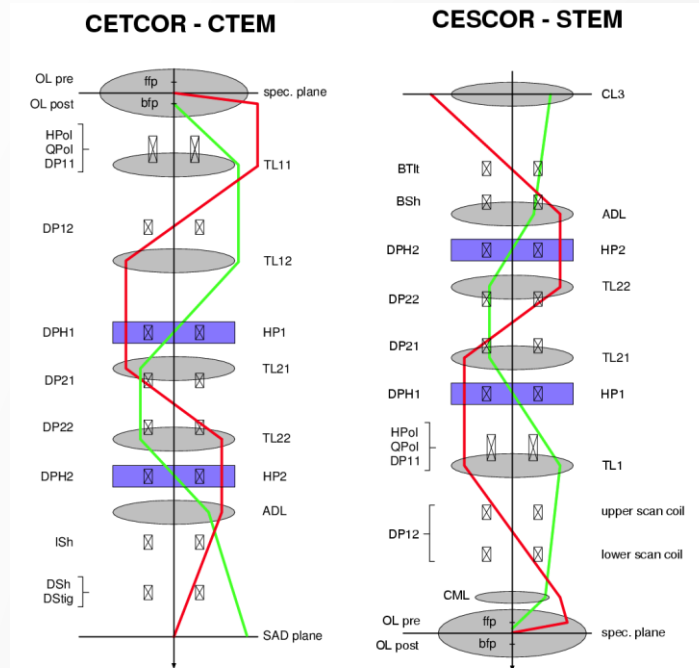
max $\beta = 0.1$ rad given TEM geometry

*** $d = 0.015$ nm

❑ ***Lens aberrations limit spatial resolution***

❑ Spherical and Chromatic
Aberration corrections allow for
0.05 nm resolution

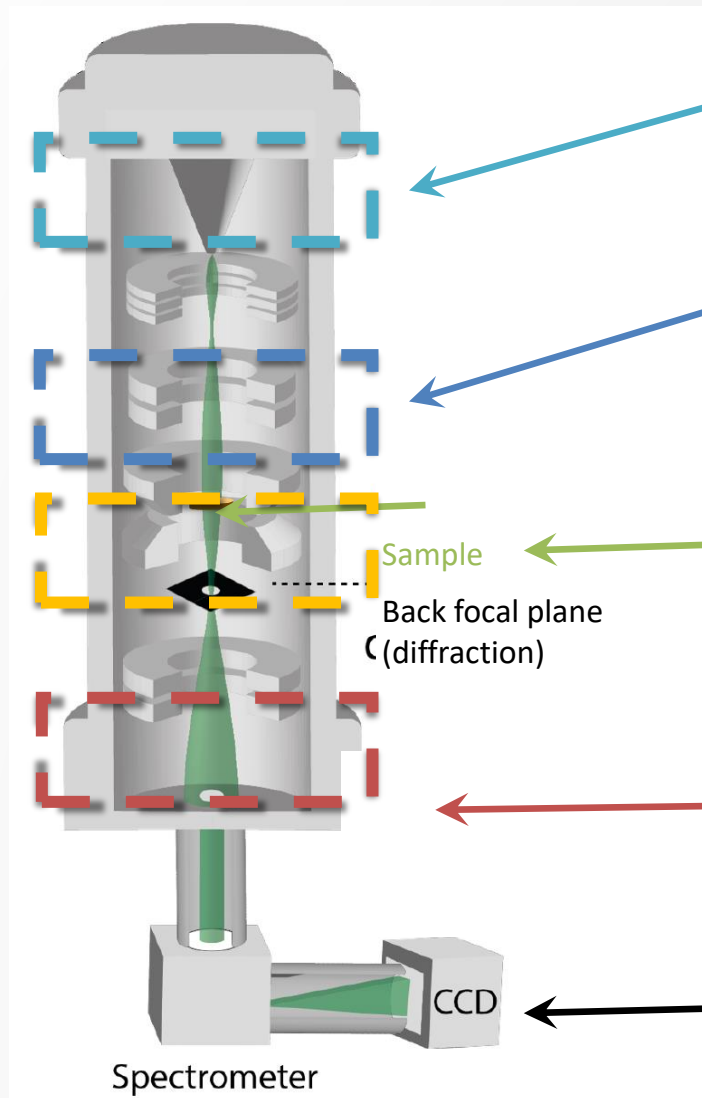
Aberration corrected (AC) HRTEM: Cs correctors



Uncorrected resolution is ~150 X diffraction limit

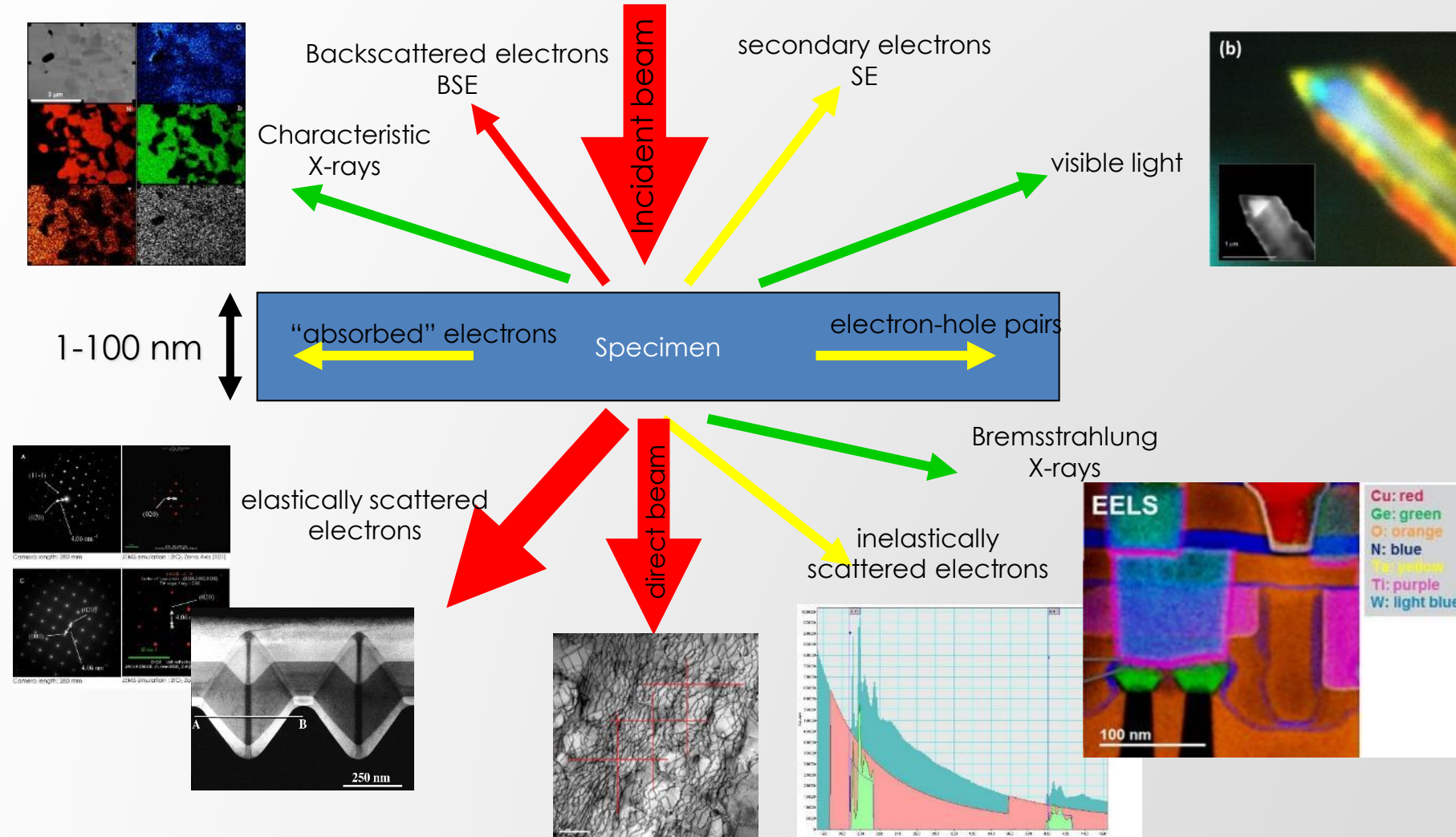
Cs-Corrected resolution is ~20 x diffraction limit

Transmission electron microscope



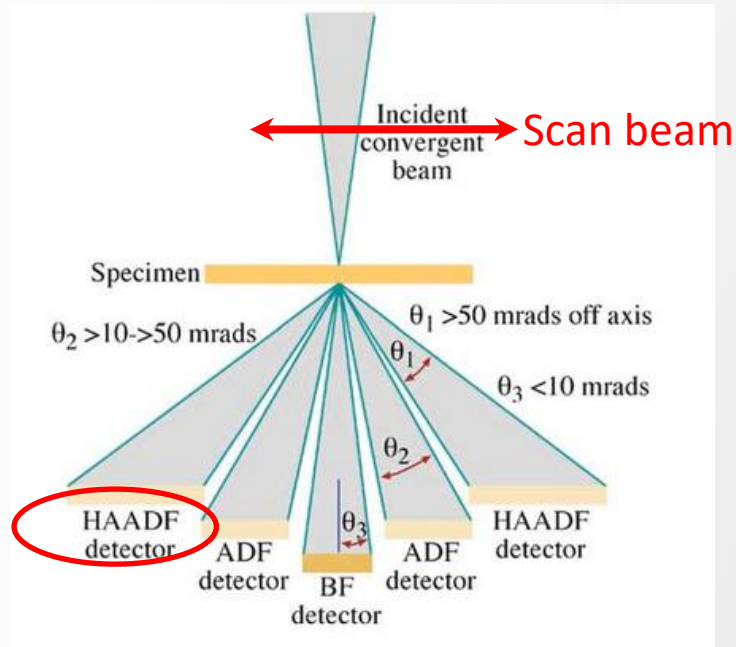
1. Gun – Thermionic or Field emission. Electrons are accelerated to different voltages (wavelengths)
2. Condenser lenses- changes spot size, illumination area, and convergence angle on the sample (forms STEM probes)
3. Objective lens – images the sample. The electron diffraction patterns are formed in the back focal plane, where the objective aperture is also located.
4. Intermediate lenses- changes modes from imaging to diffraction, magnification, and camera lengths
5. Detectors- cameras, STEM detectors, electron spectrometer

Electron-matter interactions in a thin sample



Electron-matter interactions in a thin sample: Incoherent elastic scattering - STEM

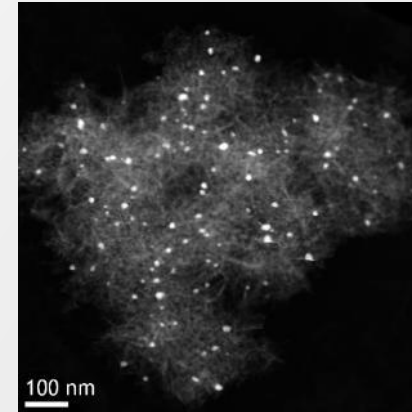
Focused e^- probe scanned on sample; disc and annular detectors in back focal (diffraction) plane



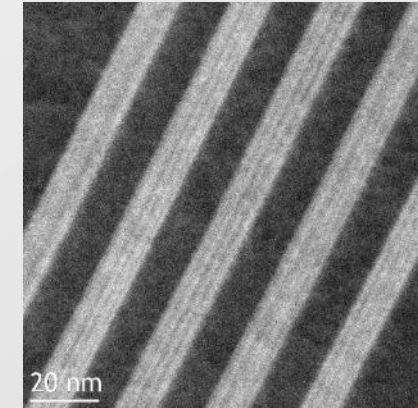
EELS spectrometer

High-angle annular dark-field =>
compositional contrast:
 $\text{intensity} \propto Z^2 t$
(thickness t , atomic number Z)

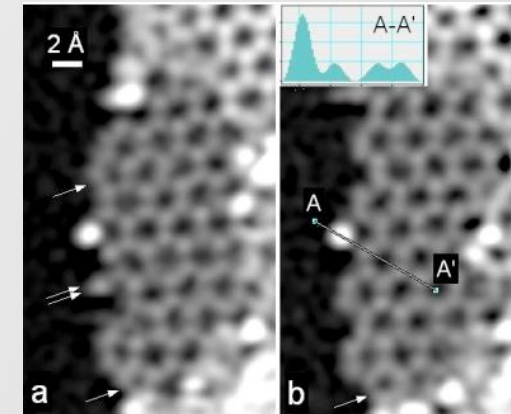
Z-contrast examples:



Pt catalyst on Al_2O_3

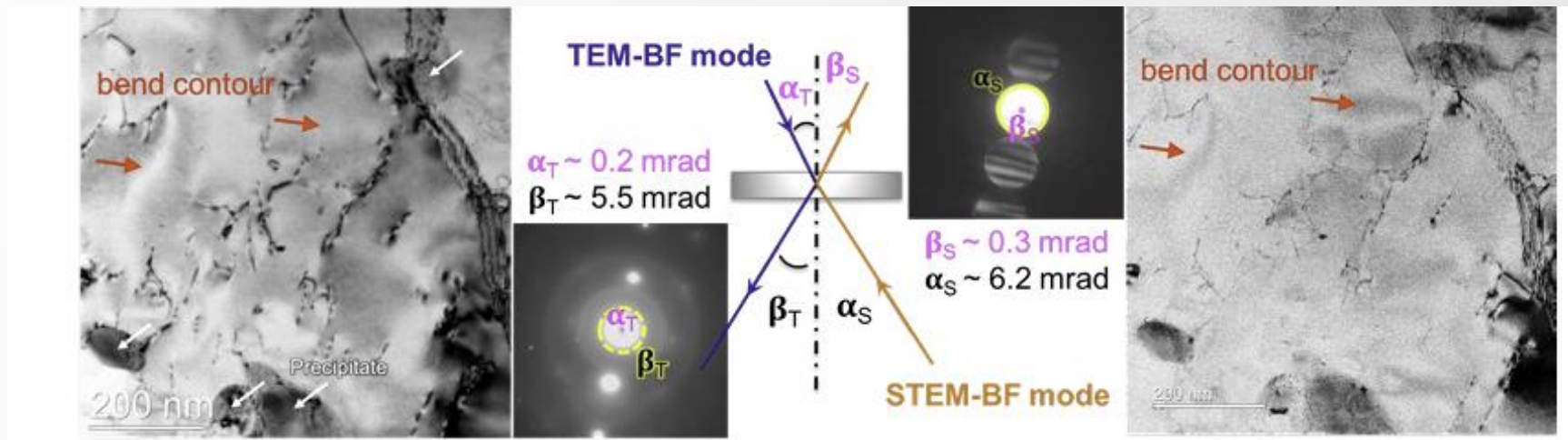


Si-Ge/Si multilayer

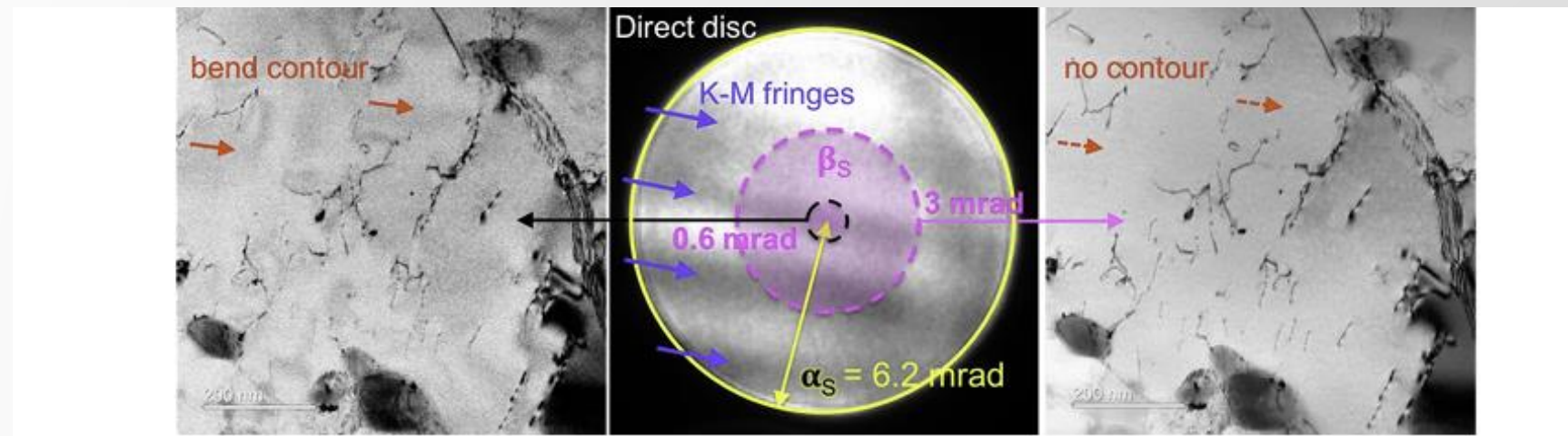


Cs-ordered - graphene with
dopant atoms (Krivanek et al., Nion)

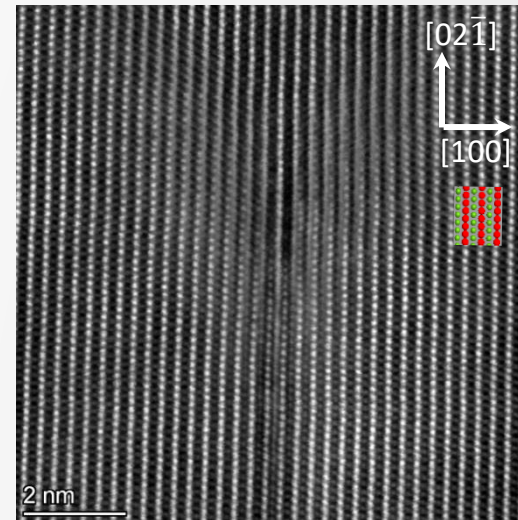
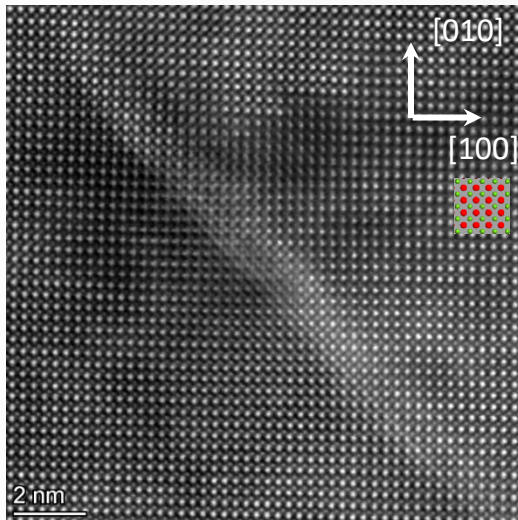
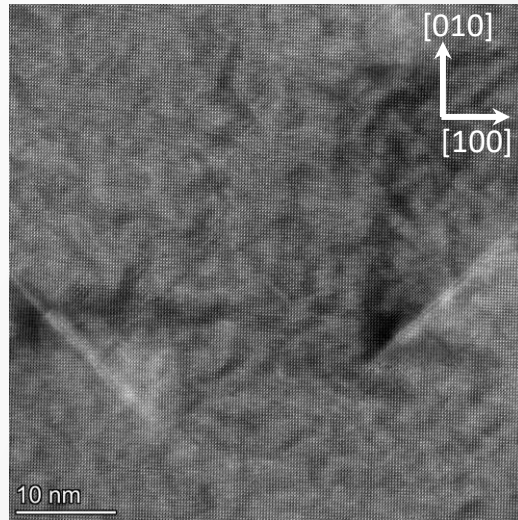
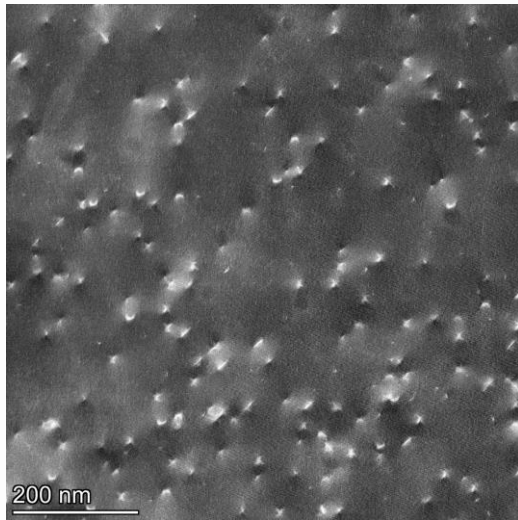
STEM imaging mode suppresses bend contours



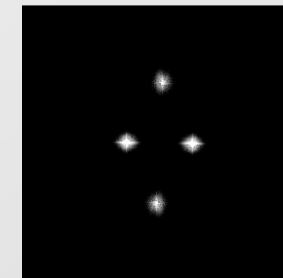
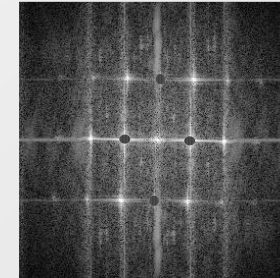
Bend Contour contrast is suppressed when $\beta_S \approx \alpha_S$



HR-STEM images of the Dislocations

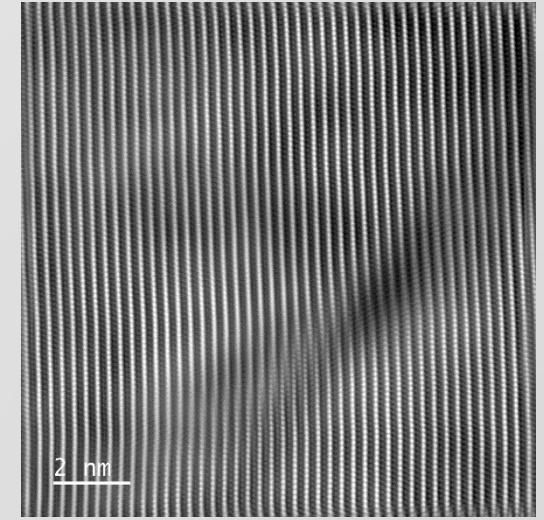
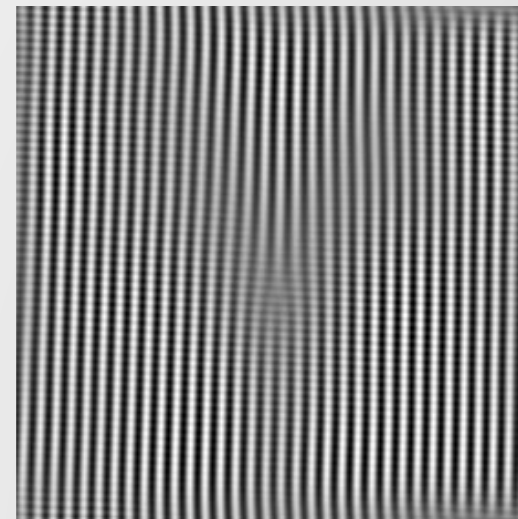


Fourier Filtering



$$\vec{b} = a[100]$$

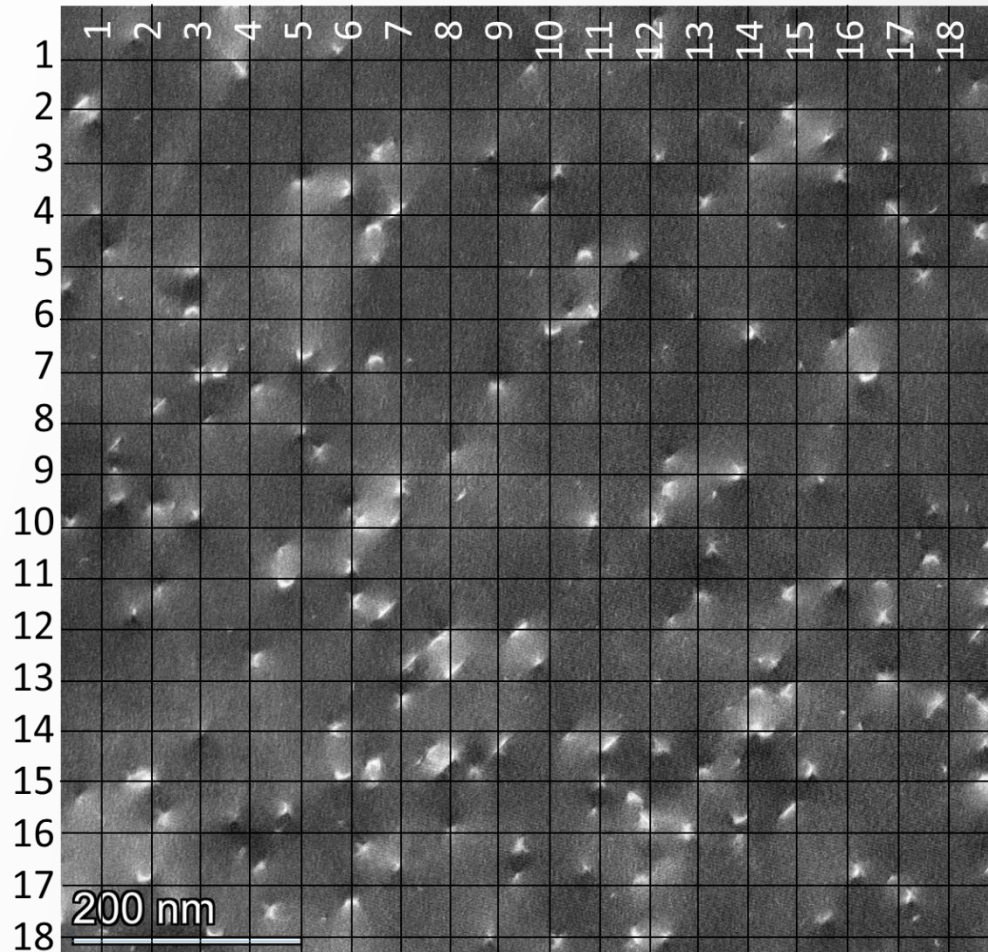
$$\vec{b} = a[111]$$



Dislocation density measurements (Orowan equation)

HAADF $\beta_S(24\text{mrad}) \approx \alpha_S(20\text{mrad})$

$$\Lambda \approx 5 \times 10^9 \text{ cm}^{-2}$$



Line Intercept Method

- Make a grid having a total line length L
- Count the number of intersections between a given grid and the dislocations, N
- Measure TEM sample thickness, t (EELS, CBED, X-ray reflection, etc.)
- The dislocation density, Λ , is given by the following equation.

$$\Lambda = 2N/tL$$

- This method is valid for dislocation density in the metal is less than 10^{14} cm^{-2} .